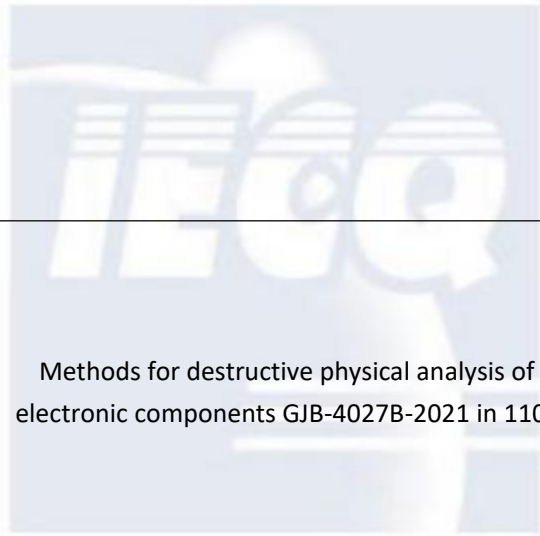


附表 3-2:

批准证书附件

Lab: Juyue Inspection Technology Co., Ltd

Add: Room 101, Building 2, No. 1388 Zhangdong Road, Shanghai

No	Products, Materials	Items, Parameter		Title, Code of specification, standard or method used	Restriction or limitation	measuring capacity	Note
		No	Items, Parameter				
1	Electrical and electronic products/electronic semiconductor products	1	Visual inspection of appearance	Test methods and procedures for microelectronic devices GJB-548C-2021 Method 2009.2 	Measure only: magnification 3 times ~ 50 times		
		2	Decap	Methods for destructive physical analysis of military electronic components GJB-4027B-2021 in 1103 in 2.6.2			

		3	SEM Inspection	Test methods and procedures for microelectronic devices GJB-548C-2021 Method 2018.2		Resolution: 1nm The maximum size of the plane can be moved: X/Y: 50*50mm, Z: 1.5_30mm	
		4	Delayer	Test Methods and Procedures for Microelectronic Devices GJB-548C-2021 Method 5003 in 3.3.3		Sample size no exceed 8 inches	
		5	IV CURVE	Test methods and procedures for microelectronic devices GJB-548C-2021 Method 5003 in 3.2.3.3.2.4		Range: $\pm 9v$ 500mA resolution 2uA	

		6	InGaAs/OBIRCH	Test methods and procedures for microelectronic devices GJB-548C-2021 Method 5003 in 3.4(d)		Wavelength: 1300nm, detection voltage range: 0~20v, detection current capacity: 0-100mA	
		7	Cross-section Polish	Test methods and procedures for microelectronic devices GJB-548C-2021 method 5003 in 3.3.2			
		8	Probe Test	Test Methods and Procedures for Microelectronic Devices GJB-548C-2021 Method 5003 in 3.2.12			

		9	EDS Analysis	Test methods and procedures for microelectronic devices GJB-548C-2021 Method 5003 in 3.4.e		Plane 1um, depth 2um	
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